

## Potential of Thin Film Detectors

Jessica Metcalfe Argonne National Laoratory

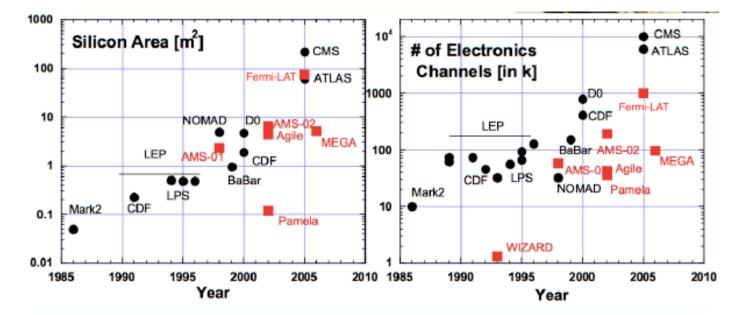
## Motivation

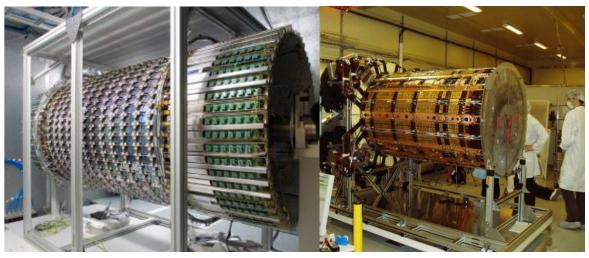


Silicon detectors are a cornerstone of High Energy Physics

Larger fractions of detectors are made with silicon

- More layers for precise tracking
- Limiting factor is often the cost
- Shift toward high precision silicon calorimeters Can we come up with an alternative that might have an advantage?

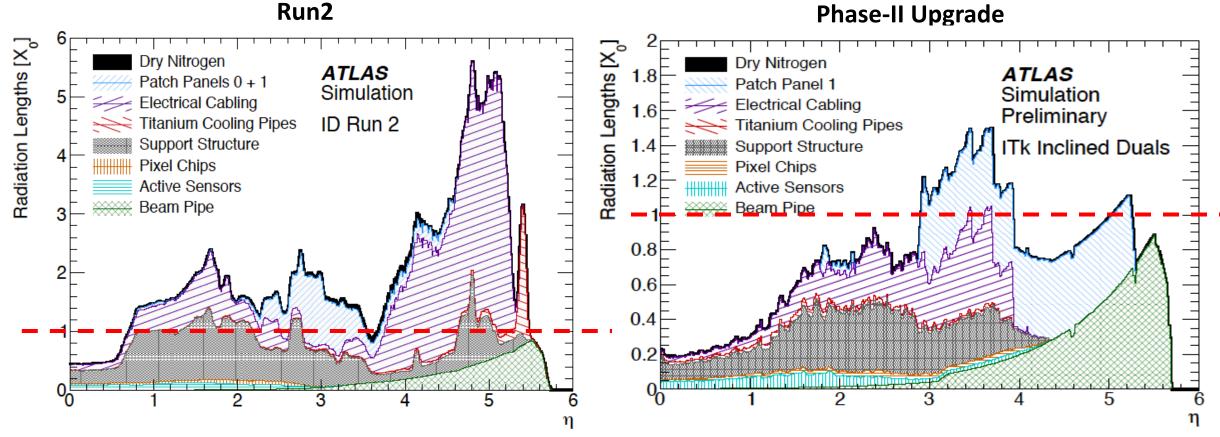




### Low Mass Detectors

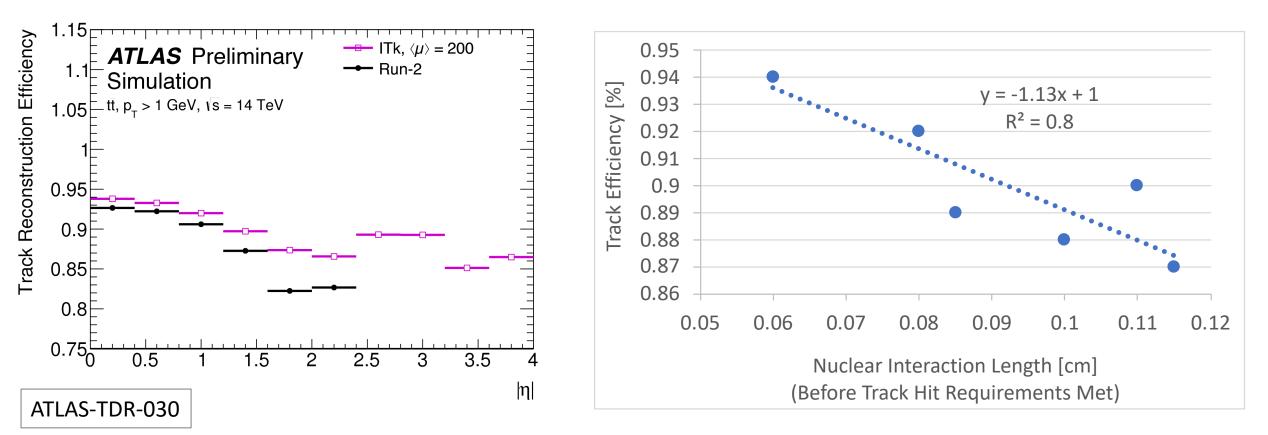


#### ATLAS-TDR-030



- Tremendous progress since the original ATLAS
- Target support structures & services
- Continue this trend





- A single silicon sensor has very high intrinsic tracking efficiency > 99%
- A detector system, however, is limited by the dead material
- Overall tracking efficiency can be optimized by reducing dead material

### Goals



- Low Mass
- Low power
- High position resolution
- Fast timing resolution
- Monolithic
- Radiation Tolerance
- Energy resolution
- Energy range: signal/noise
  - Low electron energies

- Low cost
- Reduce services
- Reduce cooling needs
- All-in-one?
  - Fewer 'sub-systems'
    - Reduce cost
    - Optimize resources
- Faster development cycle

How many features can we combine into one detector technology?

Thin Film Detectors

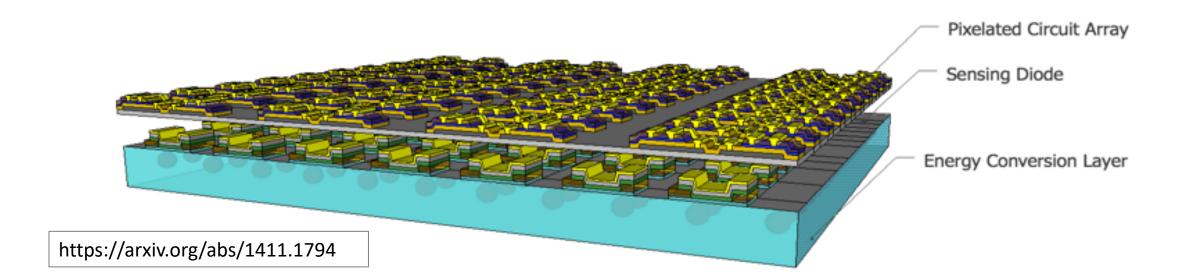


Thin Films: thin layers of materials ranging from nm to  $\mu m$ 

- Current popular applications
  - solar cells
  - LCD screens
- Thin Films for Particle Detectors:
  - Thin Film Diodes + Thin Film Transistors

Potential:

- Large area 'printing'
- Low mass
- Low cost
- Pixelated
- Integrated/monolithic design



## Thin Film Detectors: Materials

- Many potential materials with promising properties
- Catalogue potential material candidates
  - Fabrication techniques
  - Key performance parameters
  - Challenges related to individual materials

	Z	ρ	$\frac{-dE}{dx}$	MIP	$E_i$	$< N_{e-h pairs} >$
Material		$(g/cm^3)$	$[MeV/(g/cm^2)]$	in 10 $\mu$ m (keV)	(eV)	in 10 $\mu$ m
Diamond	6	3.51	1.78	6.25	13	0.5k
Si	14	2.329	1.664	3.9	3.62	1.1k
CdS	32	4.8	4.0*	19.08	6.49*	2.9k
PbS	49	7.6	6.2*	46.8	$1.98^{*}$	23.6k
ZnO	19	5.6	4.4*	24.8	$8.25^{*}$	3.0k
GaAs	32	5.32	1.4	7.45	4.2	1.8k
InP	32	4.97	4.0*	20.5	4.2	4.8k
HgI	66.5	6.4	5.6*	35.8	4.3	8.3k
InSb	50	5.78	4.9*	28.1	$1.57^{*}$	17.9k
InAs	41	5.67	4.7*	26.8	$1.94^{*}$	13.8k
HgTe	66	8.1	6.7*	54.7		
CdZnTe	43.3	6	5.0*	29.8	4.7	6.3k
IGZO	29.5	6			$7.58^{*}$	

Material	$\mu_e\left(\frac{cm^2}{V\cdot s}\right)$	$\mu_h\left(\frac{cm^2}{V\cdot s}\right)$		
Diamond	1800	1200		
Si	1350	480		
CdTe	1050	100		
CdS	340	50		
PbS	600	700		
ZnO	130			
IGZO	15	0.1		
GaAs	8000	400		
InP	4600	150		
HgI	100	4		
InSb	78000	750		
InAs	33000	460		
HgTe	22000	100		
CdZnTe	1350	120		

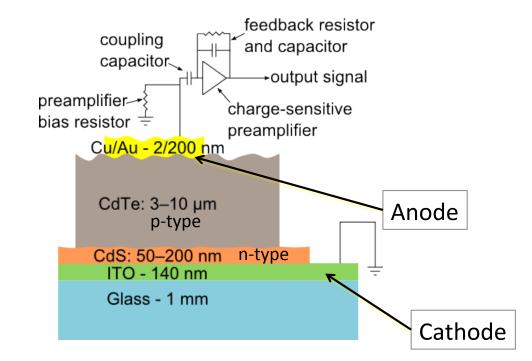
https://arxiv.org/abs/1411.1794

#### \*calculated



#### Thin Film (TF) Fabrication

- Films are grown in thin layers on a substrate with high precision
- Compare to traditional silicon that relies on growing a large crystal and then drilling, etching, etc.
- Thin Films can be fabricated using
  - chemical bath deposition
  - close-space sublimation
  - Atomic layer deposition
- TF's can be grown at least 200  $\mu$ m thick (not standard)
- Certain types of Thin Film fabrication are much less expensive
  - < \$10 per m<sup>2</sup> for a 2.5  $\mu$ m thick CdTe film
- TF can be deposited on flexible substrates such as organic polymers and plastics

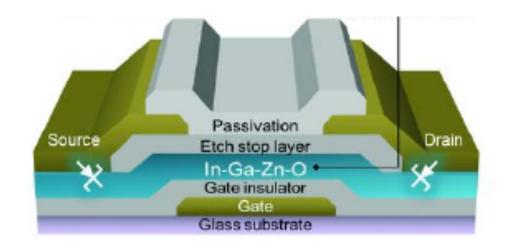






- Services is a large part of the dead material
- Low power electronics can help
- Thin Film Transistors is a large area of nanoscience development
- Explore options for HEP
  - Example:
    - High gains > 400
    - Low power < 1 nW
    - Potential integration in thin film detector

### Thin Film Transistors (TFTs): Ultralow Power



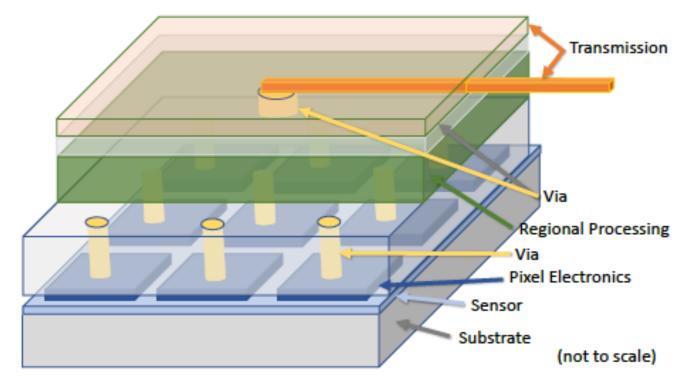
Sungsik Lee and Arokia Nathan. Subthreshold Schottky-barrier thin-film transistors with ultralow power and high intrinsic gain. Science, 354(6310):302-304, 2016.



- Combine thin film layers into a complete detector
- Consider thin film deposition techniques
  - Potential to be large area low cost like LCD screens
- Options for many different semiconductor materials
- Potential for monolithic integration of sensor + electronics
- Minimize services radiation length
- <  $1\% X/X_0$

Layer	Material	thickness $[\mu m]$	$X_0$ [cm]	$X/X_0$	$\lambda_0  [{ m cm}]$	$\lambda/\lambda_0$
Substrate	PET	250	29	0.088%	60.6	0.041%
Sensor	InSb	10	15	0.0065%	46.8	0.0021%
Electronics	InGaZnO	200	10	0.20%	45.0	0.044%
1st Via	Cu/dielectric	100	29	0.035%	60.2	0.017%
Electronics	InGaZnO	200	10	0.20%	45.0	0.044%
2nd Via	Cu/dielectric	100	25	0.04%	51.2	0.020%
Transmission	Cu/dielectric	250	20	0.13%	45.4	0.055%
Total				0.70%		0.22%

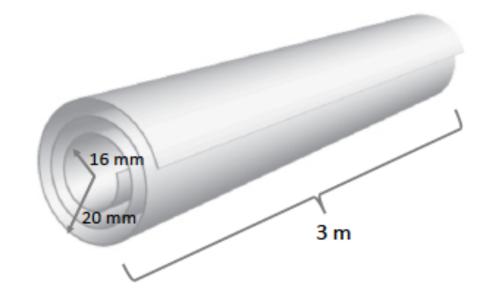
#### **Thin Film Detector Layers:**

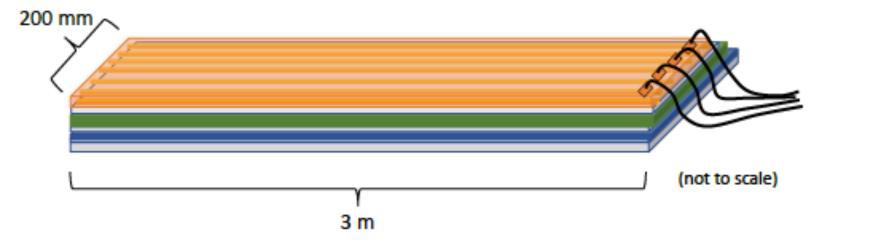




Large area design possibilities:

- Fabricate on a single flexible substrate
- Creative detector geometries like spiral cylinder roll
- Simplify detector construction process
- Move toward a single active detector system







Key Challenges:

- Sensor performance
  - Want to match silicon sensor performance
- Transistor designs
  - Compatible fabrication processes on top of sensor
  - Transistor footprint
- Vertical integration
  - How to reliably stack layers
  - Over large areas
- Transmission signal integrity over long distances
- Radiation damage
- Process industrialization



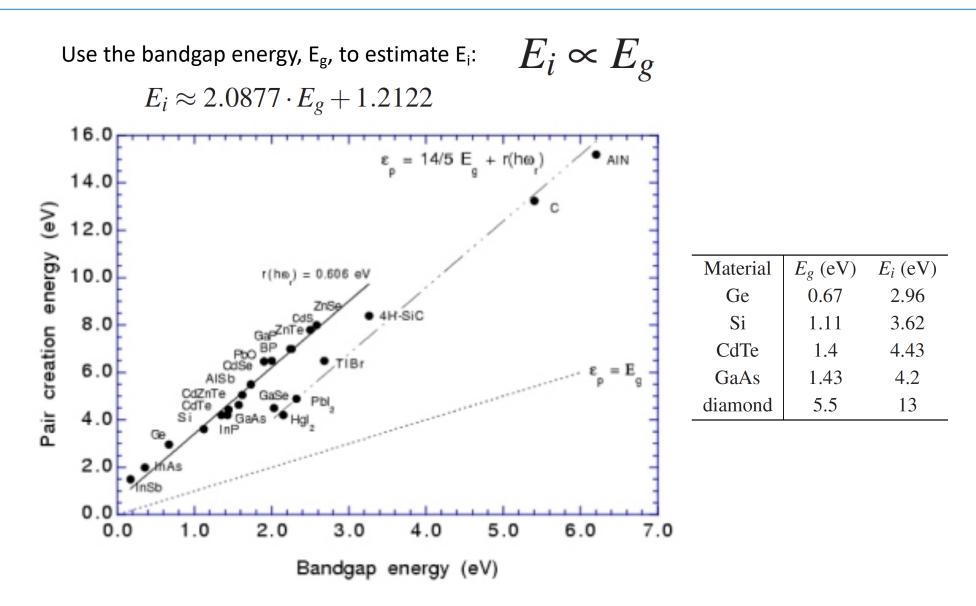
#### Potential of a Thin Film Detector design:

- Material level understanding to design and optimize a given detector design for a specific application
  - Tracking efficiency
  - Timing resolution
  - Energy resolution
  - Occupancy
  - Radiation damage
  - Etc.
- Simplify fabrication techniques to follow industrial standards
  - Large area
  - 'Printable' designs
  - monolithic
  - Low cost
  - Fast turn-over cycle
- A lot of unknowns to realize the full potential  $\rightarrow$  Long-term blue-sky R&D
- Interesting path to see where it leads



# Backup





#### **Design Goals**

Meet current tracking performance of a typical tracking detector such as ATLAS

- Charge yield 1,000 10,000 electrons
- Energy resolution 5-10% ٠
- Position resolution ~45 μm ٠
- Timing resolution 25 ns ٠
- Signal/Noise ~20

Other applications: ILC

- Timing resolution 5 ms
- Tracking precision 3 µm ٠
- $0.1\% X_0$
- ~10<sup>14</sup> 1 MeV N<sub>eq/</sub>cm<sup>2</sup>



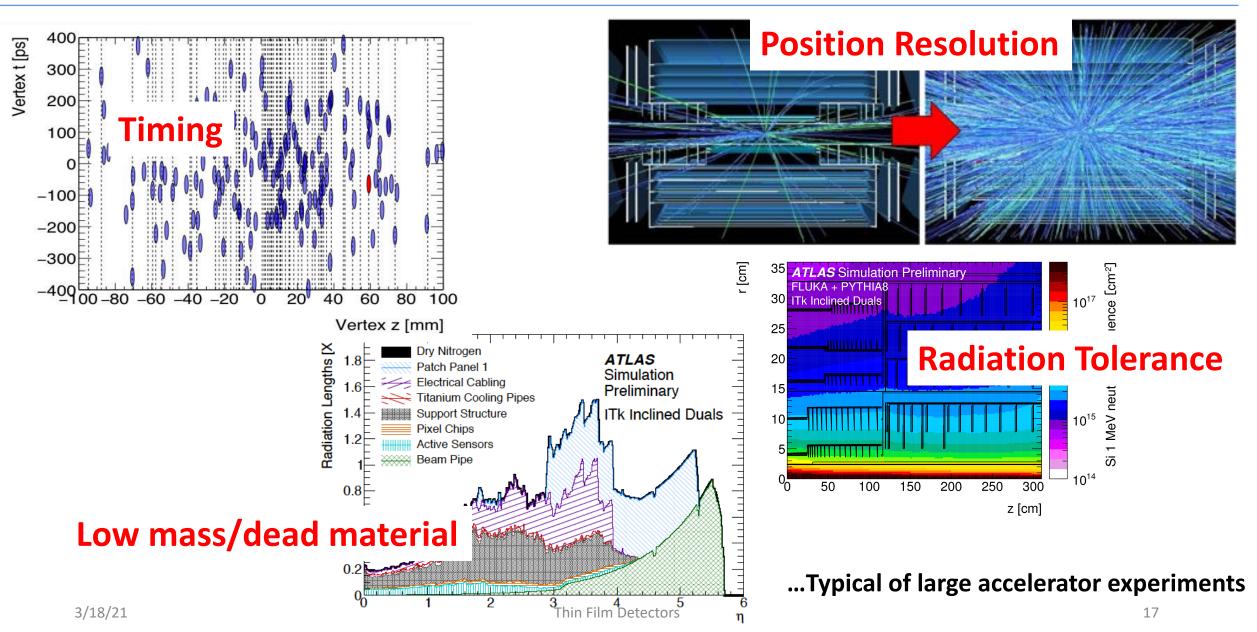
Flexible layers "printed" in large sheets

→ Possibility for unique geometries with less dead space



### Challenges

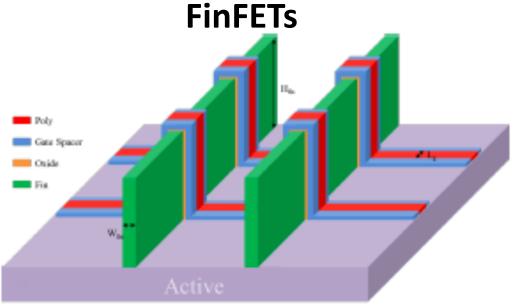




### Low Power Electronics



- FinFETs
  - ~30% less power than CMOS
  - Faster switching times
  - Energy harvesting interfaces
    - 'self-powering'
    - Can we take advantage?



Katrine Lundager, Behzad Zeinali, Mohammad Tohidi, Jens K. Madsen, and Farshad Moradi. Low Power Design for Future Wearable and Implantable Devices. J. Low Power Electron. Appl, 6(64):20, 2016.



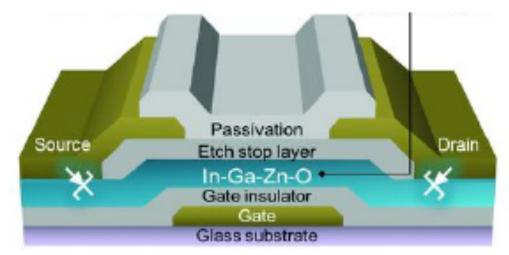
### Thin Film Transistors (TFTs)

• High gains > 400

detector

Low power < 1 nW

Potential integration in thin film



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• TFTs